



AMENDMENTS TO THE CLAIMS

1. (Currently Amended) A chemical-amplification positive-working photoresist composition which comprises, as a uniform solution in an organic solvent:

(A) a polyhydroxystyrene-based resinous ingredient of which the hydroxyl groups are partly substituted by acid-dissociable substituent groups capable of being dissociated by interacting with an acid; and

(B) a radiation-sensitive acid-generating compound capable of releasing an acid by irradiation, said acid-generating agent being selected from the group consisting of diazomethane compounds and onium salt compounds of which the anionic counterpart is a C₁-C₁₅ halogenoalkylsulfonate anion,

the resinous ingredient as the component (A) being a combination comprising (A1) a first polyhydroxystyrene resin substituted for a part from 30 to 60% of the hydroxyl groups by ~~acid-dissociable substituent~~ tert-butoxycarbonyl groups and (A2) a second ~~polyhydroxystyrene resin~~ polyhydroxystyrene resin substituted for a part from 5 to 20% of the hydroxyl groups by ~~acid-dissociable substituent~~ tert-butoxycarbonyl groups which are the same as in the first ~~polyhydroxystyrene resin~~ polyhydroxystyrene resin (A1), ~~of which the degree of substitution by the substituent groups for a part of the hydroxyl groups in the first polyhydroxystyrene resin (A1) is larger than the degree of substitution in the second polyhydroxystyrene resin (A2)~~ with the proviso that the ratio of the maximum weight-average molecular weight Mw_{max} to the minimum weight-average molecular weight $[[MW_{min}]]$ Mw_{min} in the first and second polyhydroxystyrene resins (A1) and (A2) is smaller than 1.5, and ~~wherein the overall degree of substitution in the resinous ingredient as the component (A) for a part of the hydroxyl groups by the acid-dissociable substituent groups is in the range from 5 to 60% and the acid-dissociable substituent group is selected from the group consisting of tertiary alkoxycarbonyl groups, tertiary alkyl groups, alkoxyalkyl groups and cyclic ether groups and~~

(C) an ~~amino~~ amine compound.

2 to 5. (Canceled)

6. (Currently Amended) The chemical-amplification positive-working photoresist composition as claimed in claim 5 1 in which the polyhydroxystyrene-based resinous ingredient as the component (A) is a combination of the first and second polyhydroxystyrene resins (A1) and (A2) in a weight proportion in the range from 1:9 to 9:1.

7. (Currently Amended) The chemical-amplification positive-working photoresist composition as claimed in claim 5 1 in which the polyhydroxystyrene-based resinous ingredient as the component (A) is a combination of (A1) a first polyhydroxystyrene resin substituted for from 35 to 60% of the hydroxyl groups by the acid-dissociable substituent groups and (A2) a second polyhydroxystyrene resin substituted for from 5 to 15% of the hydroxyl groups by the acid-dissociable substituent groups.

8. (Original) The chemical-amplification positive-working photoresist composition as claimed in claim 7 in which the polyhydroxystyrene-based resinous ingredient as the component (A) is a combination of the first and second polyhydroxystyrene resins (A1) and (A2) in a weight proportion in the range from 4:6 to 1:9.

9. (Canceled)

10. (Original) The chemical-amplification positive-working photoresist composition as claimed in claim 1 in which the ratio of the maximum weight-average molecular weight Mw_{max} to the minimum weight-average molecular weight Mw_{min} in the first and second polyhydroxystyrene resins (A1) and (A2) is smaller than 1.3.